

Substitute Form PTO-1449  
(Modified)U.S. Department of Commerce  
Patent and Trademark OfficeAttorney's Docket No.  
17979-034US1Application No.  
10/562,257**Information Disclosure Statement  
by Applicant**

(Use several sheets if necessary)

(37 CFR 1.98(b))

Applicant  
Shafer et al.Filing Date  
December 4, 2006Group Art Unit  
2621**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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	AB	2002/0163629	11/7/2002	Switkes et al.			
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EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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							Yes	No
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	AQQ	WO 2004/057589	7/8/2004	WIPO				
	ARR	WO 2004/107048	12/9/2004	WIPO			English abstract	
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	AVV	WO 2005/059617	6/30/2005	WIPO				
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							Yes	No
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	ATTT	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
	AUUU	Owa et al., "Immersion Lithography; its Potential Performance Issues", Proceeding of the SPIE, SPIE, Bellingham, VA, vol. 5040 no. 1, February 28, 2003, pp 724-733.

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Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AVVV	Lammers, "'Doped water' could extend 193-nm immersion litho," <i>EETimes Online</i> , <a href="http://www.eetimes.com/showArticle.jhtml?articleID=18310517">http://www.eetimes.com/showArticle.jhtml?articleID=18310517</a> , 2 pages (January 28, 2004).
	AWWW	Saurei et al., "Design of an autofocus lens for VGA 1/4-inch CCD and CMOS sensors," <i>SPIE International Symposium: Optical Systems Design</i> , St. Etienne, France, 1 page (2003)
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	AYYY	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, <a href="http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf">http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf</a> , (January 28, 2004).

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